Supporting information

Patterning and doping of Transition Metals in Tungsten Dichalcogenides

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Figure S1. (a) STEM-ADF image of Cr:WSe_{2-x} with Se flow to repair the Se vacancies through ORC reaction. The Cr substitutional dopants are highlighted by red circles. (b) Magnified STEM-ADF image of Cr:WSe₂. The atom-by-atom EELS line scan is performed along the green line. (c) EELS profile of Cr L_2 , L_3 edges extracted from the EELS line scan.



Figure S2. (a) STEM and corresponding FFT image of pristine WSe₂. Se vacancies are marked with green circles. (b) STEM and corresponding FFT image of WSe₂ covered with graphene after the ORC process. The yellow circles in the FFT image are contributed from the graphene lattice covered on WSe₂.



Figure S3. Optical images and corresponding Raman spectra of the single layer graphene mask after the ORC reaction.



Figure S4. Raman and PL mapping of the unmasked region where the WSe₂ was transformed into Cr:WS₂ completely after the ORC reaction. The Raman and PL mappings were plotted regarded to the integrated WS₂ E_{2g}^{1} peak (325~275 cm⁻¹) and the

WS₂ exciton peak ($1.9 \sim 2.1 \text{ eV}$).



Figure S5. AFM image of $Cr:WS_2$. The height of the $Cr:WS_2$ is about 1 nm and the surface is uniform without extra layer grown on the surface after the ORC reaction.



Figure S6. (a,b) STEM images of 0.4% Cr-doped WSe₂ at different magnifications. (c,d)



STEM images of 1% Cr-doped WSe₂ at different magnifications.

Figure S7. To make lateral heterostructures, graphene is used as the mask and transferred onto a monolayer WSe_2 film. The exposed WSe_2 areas allow for ORC reaction. After the ORC reaction with the supply of Mo and S precursors, the exposed WSe_2 stripes can be nearly converted into MoS_2 .



Figure S8. Raman spectra before the ORC reactions with the supply of Mo and S precursors. (a) Raman spectrum acquired on the area of exposed WSe₂. (b) Raman spectra acquired on the area of Gr/WSe_2 . The figure insets in (a) and (b) show the optical microscopy image of the patterned Gr mask on WSe₂.



Figure S9. Raman spectra and optical microscopy images of the patterned Gr mask on WSe₂ after the ORC reactions with the supply of Mo and S precursors. (a) and (c) show the optical microscopy images of the area where Raman spectra were acquired. (b) and (d) show, respectively, the Raman spectrum acquired on the exposed and masked areas of Gr/WSe₂. On the exposed area, the Raman characteristic peaks of WSe₂ vanish and is replaced by those of MoS₂ after the ORC reaction. On the contrary, the Raman characteristic peaks of WSe₂ on the Gr-masked areas remain unchanged after the ORC reaction.